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IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF :
HIROYUKI YANO ET AL : EXAMINER: DEO, D.V.
SERIAL NO: 09/531,163 :
FILED: MARCH 17, 2000 : GROUP ART UNIT: 1765
FOR: AQUEOUS DISPERSION, :
AQUEOUS DISPERSION FOR
CHEMICAL MECHANICAL
POLISHING USED FOR
MANUFACTURE OF
SEMICONDUCTOR DEVICES,
METHOD FOR MANUFACTURE
OF SEMICONDUCTOR DEVICES,
AND METHOD FOR FORMATION
OF EMBEDDED WIRING

REQUEST FOR RECONSIDERATION

COMMISSIONER FOR PATENTS
ALEXANDRIA, VIRGINIA 22313

SIR:

Responsive to the Office Action of April 30, 2003, Applicants respectfully request reconsideration of the above-identified application in view of the following amendment and remarks.

IN THE CLAIMS

Please cancel Claims 61-80.

Please add the following new claims.

81. (New) A dispersion comprising polymer particles, inorganic particles and water,
wherein the zeta potential of said polymer particles and the zeta potential of said inorganic

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